Supplementary Materials: Experimental and Modeling Study of the Fabrication of Mg Nano-Sculpted Films by Magnetron Sputtering Combined with Glancing Angle Deposition

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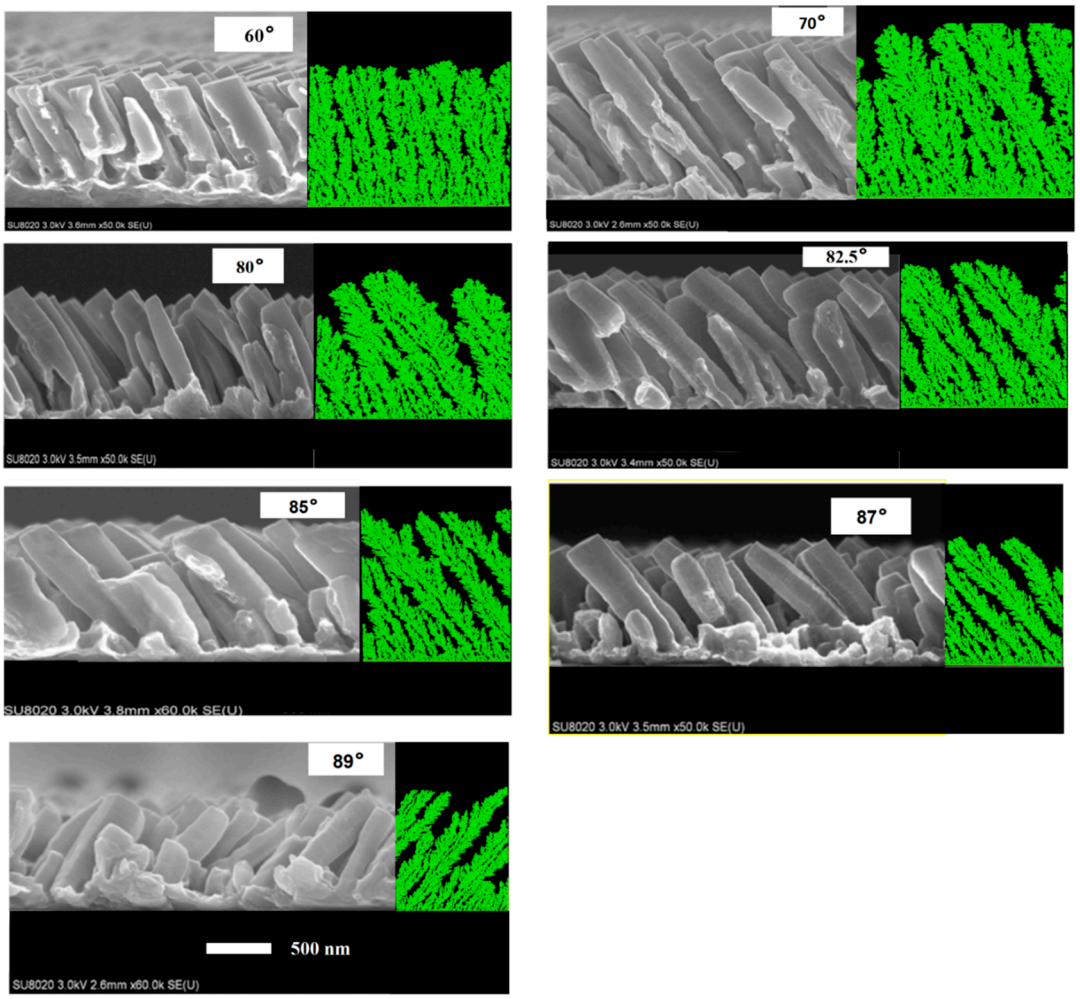

Figure S1. SEM cross-section view and of Mg films deposited for P_{Tot} = 0.26 Pa and varying α from 60° to 89°. The green images correspond to the structures calculated by using Mkc modeling.

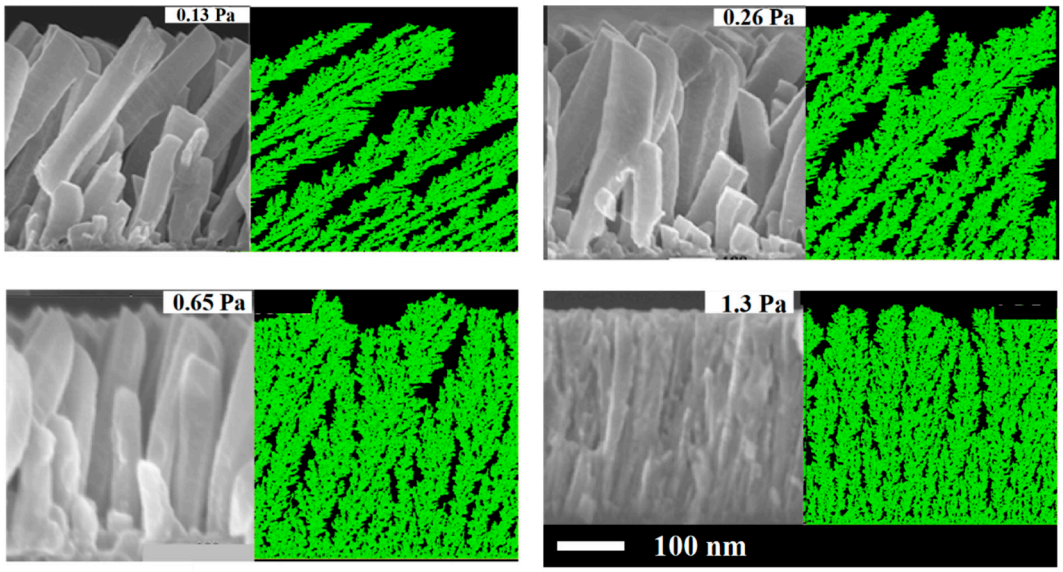

Figure S2. SEM cross-section view and of Mg films deposited for α = 85° and varying P_{Tot} from 0.13 Pa to 1.3 Pa. The green images correspond to the structures calculated by using Mkc modeling.